

Full title of workshop:

Advanced plasma processing techniques: Etch, deposition and growth for optimized device performance

Chairs of workshop:

Dr Harm Knoops, Eindhoven University of Technology

Sponsors of Workshop (Companies and/or Research Projects):

Oxford Instruments Plasma Technology

A brief descriptions of the technical scope of the workshop (up to 500 words)

Description:

Plasma processing is an essential tool for making the latest optoelectronic devices. From dry etching of laser facets to high density passivation understanding how the plasma can effect your device is vital to achieving the highest quality. Oxford Instruments Plasma Technology is at the forefront of plasma processing with a long history of developing innovative solutions to enable device performance to be pushed to the next level. This workshop will detail some of these latest developments with talks on plasma etching, Atomic Layer Deposition (ALD) and ICP CVD of dielectric films. Along side this users will detail their experiences and show how they have used our tools to deliver devices.

Experts from the UK and local users will be here to share their knowledge in an open environment so please come along and enjoy the talks but also to ask any questions that you have.